

ABSTRACT  
SINTERED COMPACT SPUTTERING TARGET

5        Provided is a sintered compact sputtering target including a metal base containing Co and Cr as the metal components and an oxide dispersed in the base, wherein the sputtering target has a structure in which a region (A) containing Co oxide dispersed in Co and a region (D) containing Cr oxide and being present in the periphery of the region (A) are included in the metal base.

10       Further provided is a method of producing a sintered compact sputtering target including a metal base containing Co and Cr as the metal components and an oxide dispersed in the base, the method including mixing a powder prepared by pulverizing a sintered compact containing Co oxide dispersed in Co, a Co powder, and a Cr powder; and pressure-sintering the resulting powder mixture to provide a  
15       sputtering target having a structure in which a region (A) containing Co oxide dispersed in Co and a region (D) containing Cr oxide and being present in the periphery of the region (A) are included in the metal base.

      By this means, a sputtering target is disclosed which has a required amount of Co oxide remaining and has sufficient sintering density to decrease the occurrence of particles during the sintering.

20       [Selected Drawing] Fig. 2